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2015 July



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 Patent type 	\sim	>株式会社ニコン	736								
Kind Code	> Fujitsu Limited										
 Assignee 	Assignee V Nikon Corporation										
 Inventor 	\sim	■ All on this page K < 1 / 14 > > 50 items per page ∨									
Agent	~	■ 1. Projection o	ptical system, exposure	apparatus, and exposure method							
Primary Examiner	· •	1	Pub./Issue No.:		Inventor:	IPC:					
USPC	\sim		US9086635B2 +	Click to open patent	Omura Yasuhiro	G02B 17 <mark>'</mark> 00 +4					
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(5564) H04N005/2 (5552) G02B006/4 (4900) G02B006/2	225 42 26		Assignee: Nikon Corporation		-						
(4264) G02B006/1 (3365) G02B006/0 (3088) G02B007/0 (2981) G02B006/3 (2970) H04N007/2	12 00 02 34	A catadioptric projection which the substrate is system is arranged in a second plane by the lig	n optical system includes a p arranged. Two mirrors are an an optical path of the light bear ht beam from the two mirrors.	lurality of lenses which are arranged betwee ranged in an optical path of the light beam m between the two mirrors and the second p The dioptric optical system includes a first n	en a first plane on which the pattern is between the plurality of lenses and th plane the dioptric optical system formin negative lens and a second negative le	s arranged and a second plane on ne second plane. A dioptric optical g the image of the pattern onto the ns, the second negative lens being					

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Inventor	\sim	1		US9054812B2	Optical modu	e	2015-06-09	14/192294	2014-02-27	FUJITSU LI	MITED	
Agent	\sim	2		US9025914B2	Optical modu	e	2015-05-05	14/190379	2014-02-26	Fujitsu Limit	ted	
Primary Examiner	\sim	3		US20150117818A1	SPOT SIZE C	ONVERTER AND OPTICAL	2015-04-30	14/488727	2014-09-17	FUJITSU LI	MITED	
• USPC	\sim	4		US9002147B2	Optical semic	onductor device	2015-04-07	14/474987	2014-09-02	Fujitsu Limit	ted	
• IPC	\sim	5		US8920042B2	Optical conne	ctor, optical fiber incorporatin	2014-12-30	13/359871	2012-01-27	Fujitsu Limit	ted +1	
• LOC	\sim	6		US8891919B2	Optical device	e, optical connector, and optic	2014-11-18	13/453117	2012-04-23	Fujitsu Limit	ted	
• CPC	\sim	7		US8882362B2	Methods for c	ptical device including transp	2014-11-11	14/184028	2014-02-19	Fujitsu Limit	ted	
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